§ 63.1434

site waste and recovery operations in 40 CFR part 63, subpart DD, with respect to the received material.

- (b) Maintenance wastewater. The owner or operator of each affected source shall comply with the HON maintenance wastewater requirements in §63.105, with the exceptions noted in paragraphs (b) (1), (2), and (3) of this section.
- (1) When the HON maintenance wastewater provisions in §63.105(a) refer to "organic HAPs listed in Table 9 of subpart G of this part," the owner or operator is only required to consider compounds that meet the definition of organic HAP in §63.1423 and that are listed in Table 9 of 40 CFR part 63, subpart G, for the purposes of this subpart.
- (2) When the term "maintenance wastewater" is used in the HON maintenance wastewater provisions in §63.105, the definition of "maintenance wastewater" in §63.1423 shall apply, for the purposes of this subpart.
- (3) When the term "wastewater" is used in the HON maintenance wastewater provisions in §63.105, the definition of "wastewater" in §63.1423 shall apply, for the purposes of this subpart.
- (c) Compliance date. The compliance date for the affected source subject to the provisions of this section is specified in §63.1422.

[64 FR 29439, June 1, 1999, as amended at 65 FR 26501, May 8, 2000]

§63.1434 Equipment leak provisions.

- (a) The owner or operator of each affected source shall comply with the HON equipment leak requirements in 40 CFR part 63, subpart H for all equipment in organic HAP service, except as specified in paragraphs (b) through (g) of this section.
- (b) The compliance date for the equipment leak provisions in this section is provided in §63.1422(d).
- (c) [Reserved]
- (d) When the HON equipment leak Initial Notification requirements contained in §63.182(a)(1) and §63.182(b) are referred to in 40 CFR part 63, subpart H, the owner or operator shall comply with the Initial Notification requirements contained in §63.1439(e)(3), for the purposes of this subpart. The Initial Notification shall be submitted no later than June 1, 2000 for existing

sources, as stated in $\S63.1439(e)(3)(ii)(A)$.

- (e) The HON equipment leak Notification of Compliance Status required by \$63.182(a)(2) and \$63.182(c) shall be submitted within 150 days (rather than 90 days) of the applicable compliance date specified in \$63.1422 for the equipment leak provisions. The notification may be submitted as part of the Notification of Compliance Status required by \$63.1439(e)(5).
- (f) The Periodic Reports required by §63.182(a)(3) and §63.182(d) may be submitted as part of the Periodic Reports required by §63.1439(e)(6).
- (g) If specific items of equipment, comprising part of a process unit subject to this subpart, are managed by different administrative organizations (e.g., different companies, affiliates, departments, divisions, etc.), those items of equipment may be aggregated with any PMPU within the affected source for all purposes under subpart H, providing there is no delay in achieving the applicable compliance date.
- (h) The phrase "the provisions of subparts F, I, or PPP of this part" shall apply instead of the phrase "the provisions of subparts F or I of this part," and instead of the phrase "the provisions of subpart F or I of this part" throughout §§63.163 and 63.168, for the purposes of this subpart. In addition, the phrase "subparts F, I, and PPP" shall apply instead of the phrase "subparts F and I" in §63.174(c)(2)(iii), for the purposes of this subpart.

[64 FR 29439, June 1, 1999, as amended at 65 FR 26501, May 8, 2000]

§63.1435 Heat exchanger provisions.

- (a) The owner or operator of each affected source shall comply with the requirements of §63.104 for heat exchange systems, with the exceptions noted in paragraphs (b) through (e) of this section.
- (b) When the term "chemical manufacturing process unit" is used in §63.104, the term "polyether polyols manufacturing process unit" shall apply for the purposes of this subpart. Further, when the phrase "a chemical manufacturing process unit meeting the conditions of §63.100(b)(1) through (3) of this subpart, except for chemical